

Title (en)

8-MIRRORED MICROLITHOGRAPHIC PROJECTOR LENS

Title (de)

8-SPIEGEL-MIKROLITHOGRAPHIE-PROJEKTIONSOBJEKTIV

Title (fr)

OBJECTIF DE PROJECTION PAR MICROLITHOGRAPHIE A 8 MIROIRS

Publication

**EP 1327172 A1 20030716 (DE)**

Application

**EP 01982439 A 20011019**

Priority

- DE 10052289 A 20001020
- EP 0112110 W 20011019
- US 25521600 P 20001213

Abstract (en)

[origin: WO0233467A1] The invention relates to a microlithographic projector lens for EUV-lithography with a wavelength in the range 10 - 30 nm, an incident aperture diaphragm and an emergent aperture diaphragm for the transformation of an object field in an object plane into an image field in an image plane. The invention is characterised in that the microlithographic projector lens comprises a first, second, third, fourth, fifth, sixth, seventh and eighth mirror (51-58) and the beam path from the object plane (100) to the image plane (102) is free from obscuration.

IPC 1-7

**G02B 17/06**; **G03F 7/20**

IPC 8 full level

**G02B 17/00** (2006.01); **G02B 17/06** (2006.01); **G03F 7/20** (2006.01); **H01L 21/027** (2006.01)

CPC (source: EP KR US)

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Citation (search report)

See references of WO 0233467A1

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DOCDB simple family (publication)

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DOCDB simple family (application)

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